

# Tuning Light Absorption in Core/Shell Silicon Nanowire Photovoltaic Devices through Morphological Design

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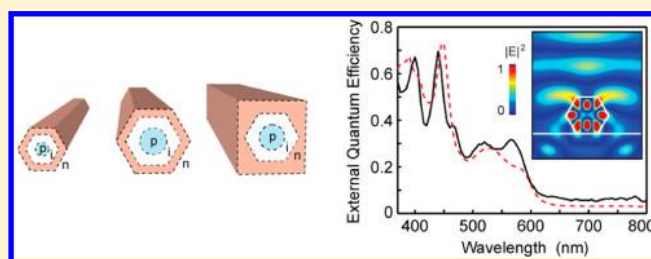
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**S** Supporting Information

**ABSTRACT:** Subwavelength diameter semiconductor nanowires can support optical resonances with anomalously large absorption cross sections, and thus tailoring these resonances to specific frequencies could enable a number of nanophotonic applications. Here, we report the design and synthesis of core/shell p-type/intrinsic/n-type (p/i/n) Si nanowires (NWs) with different sizes and cross-sectional morphologies as well as measurement and simulation of photocurrent spectra from single-NW devices fabricated from these NW building blocks.

Approximately hexagonal cross-section p/i/n coaxial NWs of various diameters (170–380 nm) were controllably synthesized by changing the Au catalyst diameter, which determines core diameter, as well as shell deposition time, which determines shell thickness. Measured polarization-resolved photocurrent spectra exhibit well-defined diameter-dependent peaks. The corresponding external quantum efficiency (EQE) spectra calculated from these data show good quantitative agreement with finite-difference time-domain (FDTD) simulations and allow assignment of the observed peaks to Fabry–Perot, whispering-gallery, and complex high-order resonant absorption modes. This comparison revealed a systematic red-shift of equivalent modes as a function of increasing NW diameter and a progressive increase in the number of resonances. In addition, tuning shell synthetic conditions to enable enhanced growth on select facets yielded NWs with approximately rectangular cross sections; analysis of transmission electron microscopy and scanning electron microscopy images demonstrate that growth of the n-type shell at 860 °C in the presence of phosphine leads to enhanced relative Si growth rates on the four {113} facets. Notably, polarization-resolved photocurrent spectra demonstrate that at longer wavelengths the rectangular cross-section NWs have narrow and significantly larger amplitude peaks with respect to similar size hexagonal NWs. A rectangular NW with a diameter of 260 nm yields a dominant mode centered at 570 nm with near-unity EQE in the transverse-electric polarized spectrum. Quantitative comparisons with FDTD simulations demonstrate that these new peaks arise from cavity modes with high symmetry that conform to the cross-sectional morphology of the rectangular NW, resulting in low optical loss of the mode. The ability to modulate absorption with changes in nanoscale morphology by controlled synthesis represents a promising route for developing new photovoltaic and optoelectronic devices.

**KEYWORDS:** Facet-selective growth, solar energy, nanoelectronic device, coaxial p/i/n nanostructure, FDTD simulations, optical resonances



Strong light confinement in nanowire (NW) structures has enabled advances in diverse photonic applications from nanolasers to photovoltaic devices.<sup>1–16</sup> For example, the optical properties of arrays of nano- and microscale wires have been exploited for enhanced light absorption in photovoltaic devices;<sup>16–19</sup> however, the ability to substantially manipulate absorption in individual nanoscale structures has not been well established. In order to quantify optical resonances supported in individual NWs, scattering<sup>20–22</sup> and absorption cross sections<sup>5,6,11,23–26</sup> have been measured or calculated. Significantly, measurement of the absolute external quantum efficiency (EQE) from NW devices has been reported only in limited instances.<sup>6,11,23</sup> We recently reported an absolute EQE value of up to ~1.2 using core/shell Si NWs with a size of ~300

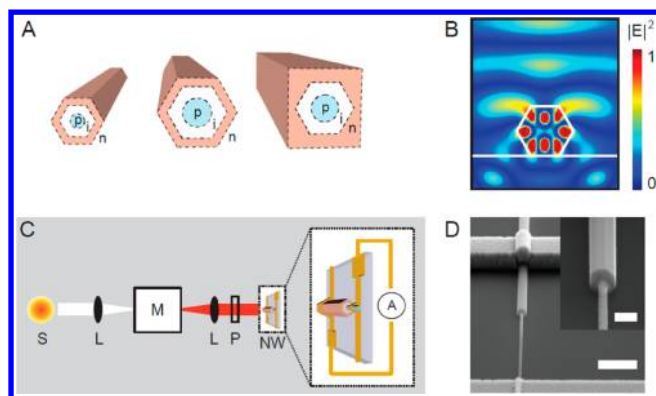
nm.<sup>6</sup> By comparison, EQE values of ~0.15 have been reported for microscale devices based on Al–Si Schottky junctions<sup>23</sup> and values of ~1.1 for devices with coaxial p–n junctions that included a backside reflector.<sup>11</sup> Several reports of relative EQE values have been reported for Si and Ge nanowire devices acting as photodetectors.<sup>5,24,25</sup>

Our integrated approach to understanding the effect of morphology on light absorption in individual p/i/n Si NWs is illustrated in Figure 1. First, we synthesized core/shell p/i/n Si

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**Figure 1.** Overview of the experimental design and concepts. (A) Schematic illustration of designed p/i/n Si NW structures, which include variations in diameter and cross-sectional morphology (hexagonal and rectangular). (B) Electric field intensity illustration of coupling between a vertically incident plane wave and highly confined resonant modes within a Si NW. (C) Diagram of the optical setup measuring the photocurrent as a function of wavelength for single-NW photovoltaic devices. The output of Xe lamp light source (S) passes through lenses (L), a monochromator (M), and a polarizer (P) and then uniformly illuminates the NW device. (D) SEM image of a representative p/i/n photovoltaic device, showing metal contacts to the p-type core (bottom of image) and n-type shell (upper left of image). Scale bar: 1  $\mu\text{m}$ . Inset: magnification of the core–shell interface showing a core diameter of  $\sim 85$  nm and shell diameter (facet to facet) of  $\sim 240$  nm. Scale bar: 200 nm.

NWs of various sizes and cross-sectional morphologies through tuning of chemical vapor deposition (CVD) growth parameters, as illustrated in Figure 1A. Single-NW devices were fabricated from these building blocks to probe how size and morphology influence the absorption of Si NWs. The Si NWs explored here had diameters ranging from 100 to 400 nm and cross-sectional morphologies varying from hexagonal to rectangular. Second, to understand the absorption features of NW cavities, we performed three-dimensional finite-difference time-domain (3-D FDTD) simulations, wherein a normally incident planewave interacts with a Si NW cavity, as shown in Figure 1B. Lastly, we characterized the optical resonances by direct measurement of the photocurrent generated from functioning NW photovoltaic devices illuminated at discrete wavelengths from 380 to 800 nm, using the optical setup depicted in Figure 1C.<sup>27</sup> Comparison of measured transverse-electric (TE) and transverse-magnetic (TM) polarized spectra, as depicted in Supporting Information Figure S1A, to those spectra obtained from FDTD simulations allows for the assignment of resonant modes excited within the NW cavity. Notably, the FDTD simulations used here provide quantitative agreement with experiment by accurately describing both the NW cross-sectional morphology and underlying substrate. In contrast, Lorentz–Mie theory is an analytical formula and, as such, can only describe a circular NW in a homogeneous medium and provide qualitative agreement with experiment.<sup>21,24,25</sup>

Core/shell Si NWs were synthesized by chemical vapor deposition (CVD) using vapor–liquid–solid (VLS) growth for the p-type core<sup>28</sup> and vapor–solid (VS) growth for intrinsic and n-type shells.<sup>6</sup> In general, we have synthesized p/i/n structures of different sizes by varying the diameter of the p-type core and thickness of the intrinsic shell.<sup>29</sup> Control over rectangular morphology through synthesis has not been reported previously, and the proposed mechanism will be

discussed below. NW photovoltaic devices were fabricated by defining metal contacts selectively to the p-type core and n-type shell following selective etching of n- and i-shells on one end of the NW, as shown in Figure 1D.

We first investigated the behavior of hexagonal cross-section p/i/n NWs as a function of nominal diameters. Scanning electron microscopy (SEM) images show this approximately hexagonal cross-sectional morphology (Figure S1B).<sup>6</sup> Photocurrent spectra were acquired by measuring the current as the wavelength of incident light was scanned from 380 to 800 nm.<sup>27</sup> EQE spectra were determined by dividing the photocurrent at a given wavelength by the incident photon flux at the same wavelength. The EQE spectra for devices with diameters of 170, 280, and 380 nm (solid black, Figure 2A) highlight several key features. First, the number of measured peaks increases with increasing NW size: 5 for the smallest device, 6 for the intermediate device, and 7 for the largest device. Second, the cutoff wavelength, the longest wavelength of a peak in the spectrum, for resonant modes shifts to longer wavelengths with increasing NW size: 565 nm for the smallest device, 635 nm for the intermediate device, and 670 nm for the largest device. Consequently, the increase in NW size produces a gradual increase in short-circuit current density ( $J_{\text{SC}}$ ), and this trend is reflected in the red points plotted in Figure 2B as a function of the diameter of the NW.<sup>27</sup>

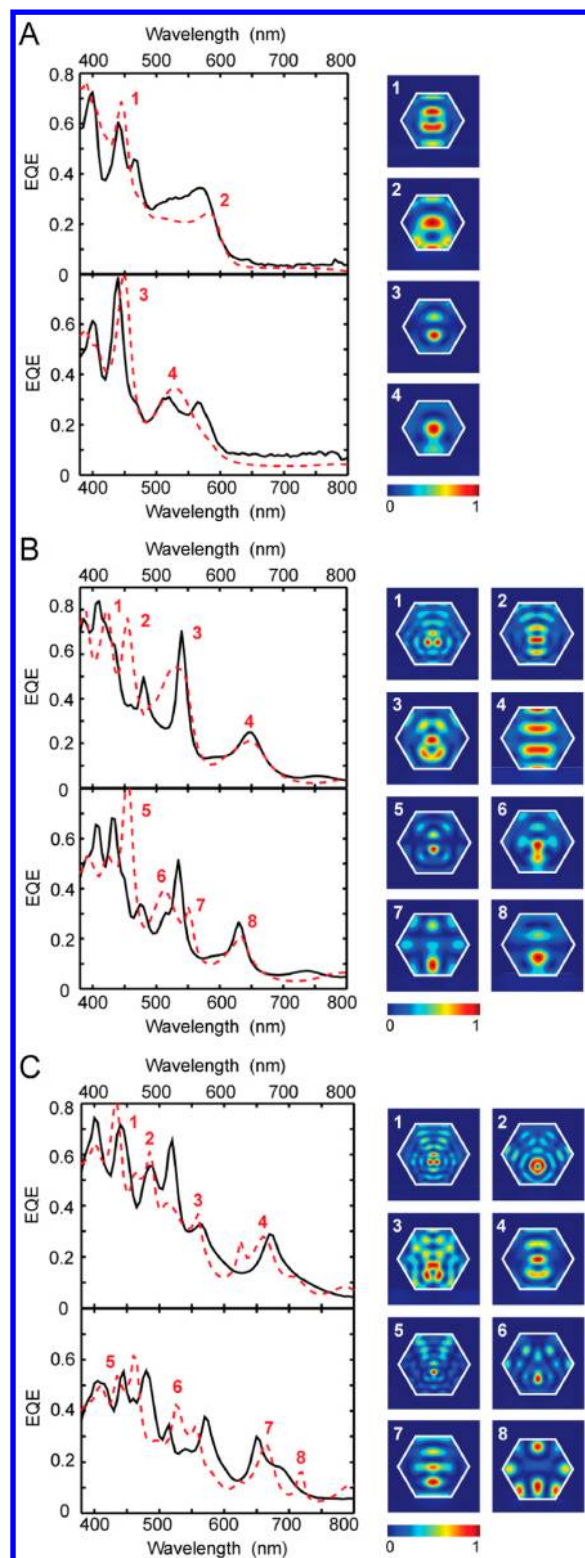
Notably, the measured EQE spectra agree well with FDTD simulations (dashed red, Figure 2A).<sup>30</sup> Both amplitudes and wavelengths of the measured peaks were reproduced accurately by the simulations, thus demonstrating that the photocurrent of the working NW device is determined by the absorption characteristics of the Si NW. Additionally, the simulations show that the same absorption modes shift to longer wavelengths with increasing NW size. For instance, the peaks at 445, 620, and 795 nm for the small, intermediate, and large sized devices, respectively, correspond to the same Fabry–Perot type modes with two antinodes in the absorption mode profile, which are marked by an asterisk and depicted in the upper, middle, and bottom insets of Figure 2A. The  $\sim 200$  nm increase in size produces a shift of  $\sim 350$  nm in wavelength for this specific mode.

In addition, Figure 2B shows the calculated total photocurrent per unit area ( $J_{\text{SC}}$ , dashed red) and per unit volume (dashed black) as a function of the diameter of the NW determined from FDTD simulations.  $J_{\text{SC}}$  increases gradually with increasing diameter of the NW with the exception of a local maximum at 140 nm in diameter. The  $J_{\text{SC}}$  calculated from simulation is in excellent agreement with the  $J_{\text{SC}}$  from experiment (red points, Figure 2B). The increase in  $J_{\text{SC}}$  for larger NWs results from an increased number of absorption peaks together with resonant modes excited at long wavelengths. Enhanced optical antenna effects from smaller NW cavities account for a local maximum in  $J_{\text{SC}}$  at the Si diameter of 140 nm (dashed red, Figure 2B).<sup>25</sup> The photocurrent per unit volume increases dramatically for devices smaller than 200 nm in diameter due to increasingly larger ratio of absorption cross section to physical cross section (dashed black, Figure 2B). These results highlight the unique capacity of NW structures to efficiently localize light in nanoscale volumes and to potentially enable low-cost photovoltaic devices through reduced material per device element.

To understand in more detail the enhanced absorption in these structures, we measured polarization-resolved photocurrent spectra for the devices of Figure 2A with diameters of

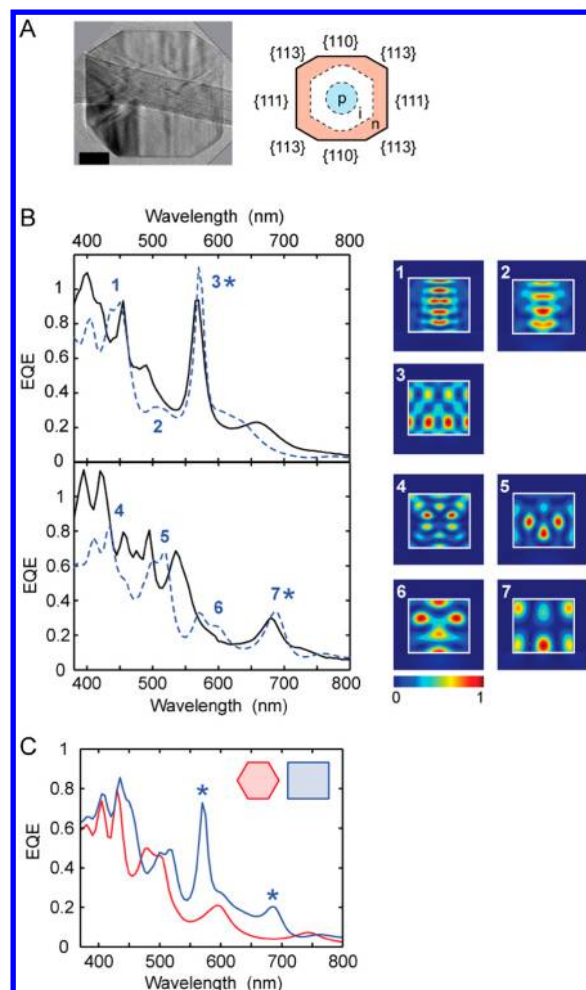






**Figure 3.** Polarization-resolved EQE spectra of hexagonal p/i/n Si NWs. (A, B, C) Left: experimental (solid black) and simulated (dashed red) EQE spectra collected with TE (top) and TM (bottom) polarization for a NW with diameter of 170 (A), 280 (B), and 380 nm (C). Right: normalized absorption mode profiles corresponding to the peaks labeled on the left.

black, Figure 4B). In the TE spectrum (top, Figure 4B), the peak centered at 570 nm shows a near-unity EQE amplitude. The peak at 680 nm in the TM absorption spectrum (bottom,



**Figure 4.** Fabrication and characterization of p/i/n Si NWs with rectangular cross-sectional morphology. (A) Left: TEM image of a rectangular p/i/n NW cross section. Scale bar: 50 nm. Right: schematic illustration of the diode structure within the rectangular NW and with faceted surfaces assigned to {110}, {113}, and {111} crystal planes. (B) Left: experimental (solid black) and simulated (dashed blue) EQE spectra measured with TE (top) and TM (bottom) polarization for a rectangular NW with a diameter of 260 nm. Absorption modes with high-order symmetry are marked by an asterisk. Right: normalized absorption mode profiles for the peaks labeled on left. (C) Simulated EQE spectra for a hexagonal (solid red) and rectangular (solid blue) NW with the same diameter of 260 nm. An aspect ratio of 0.87 is used for both morphologies. Inset: schematic illustration of the two simulated structures.

Figure 4B) shows an EQE value of  $\sim 0.3$ , which is significant given that crystalline Si has a very low extinction coefficient at this long wavelength. For the peak centered at 570 nm (680 nm), an equivalent EQE value in bulk Si could only be achieved by more than  $\sim 3.3 \mu\text{m}$  ( $\sim 1.3 \mu\text{m}$ ) of material. The same two high-amplitude modes were also identified in the spectra of a  $\sim 50$  nm smaller rectangular NW with the same aspect ratio (Figure S3A). These pronounced peaks were reproduced in the simulated EQE spectra (dashed blue, Figure 4B) of the rectangular NW. Notably, the pronounced peaks centered at long wavelengths correspond to high-symmetry cavity modes (marked by an asterisk and depicted in Figure 4B).

The distinct absorption properties of the rectangular NW are most apparent when comparing the simulated EQE spectrum of a rectangular NW to the spectrum of a hexagonal NW with



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- (27) A solar simulator (150 W, Newport Oriel) with AM1.5G filter and calibrated 1 sun intensity was used in conjunction with a probe station (TTP-4, Desert Cryogenics) and semiconductor parameter analyzer (4156C, Agilent Technologies) to obtain all device transport characteristics. For EQE spectra, devices were wire-bonded to a chip carrier and interfaced with a home-built optical setup utilizing the solar simulator with AM1.5G filter as illumination source and a spectrometer (SpectraPro 300i, Acton Research) for narrow-band illumination of the NW devices concurrent with measurement of  $J_{SC}$  at each wavelength. For comparison between experimental and simulated  $J_{SC}$  values, the experimental  $J_{SC}$  values were determined from the experimental EQE spectra from 380 to 800 nm and the reference AM1.5G spectrum. Ultrathin NW cross sections for TEM were prepared by embedding NWs within epoxy resin (Epo-Tek 353ND, Epoxy Technology) and then microtoming ~40 nm thick sections using a diamond blade.
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- (29) Si core/shell NWs were synthesized in a quartz tube furnace connected to a vacuum pump (base pressure  $3 \times 10^{-3}$  Torr) and gas manifold with silane ( $\text{SiH}_4$ ), diborane ( $\text{B}_2\text{H}_6$ ; 100 ppm in  $\text{H}_2$ ), phosphine ( $\text{PH}_3$ ; 1000 ppm in  $\text{H}_2$ ), and  $\text{H}_2$  (99.999% semiconductor grade). Crystalline Si p-type NW cores were synthesized by Au-catalyzed VLS growth using 50 nm Au nanoparticles (Ted Pella) for small NWs and 100 nm nanoparticles for intermediate and large NWs. Nanoparticles were dispersed on Si wafers with 600 nm thermal oxide (Nova Electronic Materials) and placed in the quartz tube furnace for core growth for 2.5 h at 450 °C with a pressure of 40 Torr using flow rates of 1 standard cubic centimeter per minute (sccm)  $\text{SiH}_4$ , 10 sccm  $\text{B}_2\text{H}_6$ , and 60 sccm  $\text{H}_2$ . Shell growth was performed in the same reactor using VS growth conditions at 775 °C with a pressure of 25 Torr and 0.15 sccm  $\text{SiH}_4$  and 60 sccm  $\text{H}_2$  for intrinsic shells and additional 0.75 sccm  $\text{PH}_3$  for n-type shells. Typical shell growth times were 25 min for intrinsic and 15 min for n-type. Rectangular NWs were produced by increasing the time and temperature used for the n-type shell to 40 min and 860 °C, respectively. Conformal  $\text{SiO}_2$  dielectric shells were deposited via plasma-enhanced chemical vapor deposition (PECVD) over as-grown NWs on the growth substrate. NWs were dry transferred to Si substrates coated with 100 nm thermal oxide and 200 nm  $\text{Si}_3\text{N}_4$  (University Wafer). SU-8 was patterned by electron beam lithography over NWs to act as an etch mask during wet-chemical etch of NWs with buffered HF (BHF) to remove  $\text{SiO}_2$  and with KOH (60 °C) to remove the Si shells. SU-8 was subsequently removed with a UV/ozone asher, and residual PECVD deposited  $\text{SiO}_2$  was removed with a BHF etch. Electron-beam lithography and thermal evaporation of ~350 nm thick Ti/Pd were used to form selective contacts to the etched (p-type) Si core and unetched (n-type) Si shell.
- (30) For a vertically incident plane wave with TE and TM polarizations, the absorption cross section of a NW was determined from integrating  $J \cdot E$  at each grid point over one optical period, where  $J$  and  $E$  are the polarization current density and electric field, respectively. The absorption efficiency was defined by the ratio of the NW absorption cross section to the projected area. EQE was calculated by multiplying the absorption efficiency by internal quantum efficiency (IQE), where IQE was assumed to be 0.8. The short-circuit current density ( $J_{SC}$ ) at a specific wavelength was calculated as follows:  $J_{SC}(\lambda) = \text{EQE} \times (\text{spectral irradiance of AM 1.5G spectrum at 1 sun solar intensity}) \times \lambda/1.24$ . The total  $J_{SC}$  was obtained by integrating  $J_{SC}(\lambda)$  over the wavelength range of 380–800 nm. For hexagonal (rectangular) NWs, a spatial resolution of  $5/\sqrt{3}$  (5), 5, and 5 nm for  $x$ ,  $y$ , and  $z$ , respectively, was used to represent the volume element for our hexagonal (rectangular) cross section of a NW, where  $y$  lies along the NW axis and  $z$  lies along the propagation direction of the incident plane wave. All NW simulations included the same substrates used in the experiment.
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